WHAT IS CLAIMED IS:

1. An evaporation apparatus, comprising:

a holder configured to hold a substrate;

a source configured to evaporate an evaporation material which is to be deposited on the substrate;

a first sensor configured to detect evaporation rates of the evaporation material at a plurality of detection positions,

wherein the plurality of detection positions are arranged along a detection line, and the detection extends substantially orthogonal to a surface of the substrate on which the evaporation material is to be deposited,

and wherein the source has an opening from which the evaporation material is discharged, and a projection of the detection line on a projection plane is separated from a projection of the opening of the source on the projection plane, wherein the projection plane is substantially parallel with the surface of the substrate;

a calculator unit configured to estimate an evaporation angle based on the detected evaporation rates of the evaporation material at the plurality of detection positions; and

an actuator configured to move the source based on the estimated evaporation angle.

2. The evaporation apparatus of claim 1, wherein the first sensor is movable along the detection line.

3. The evaporation apparatus of claim 1, wherein the detection line is substantially straight.

4. The evaporation apparatus of claim 1, wherein the detection line slopes relative to a normal direction orthogonal to a surface of the substrate on which the evaporation material is to be deposited.

5. The evaporation apparatus of claim 1, further comprising:

a chamber configured to accommodate the holder, the source, and the first sensor, wherein the holder is proximate to a wall of the chamber, and the plurality of detection positions are located between the source and the wall of the chamber.

6. The evaporation apparatus of claim 1, wherein the calculator unit comprises:

a comparator unit configured to compare the detected evaporation rates with reference evaporation rates respectively, wherein the actuator is configured to move the source based on differences between the detected evaporation rates and the reference evaporation rates.

7. The evaporation apparatus of claim 1, further comprising:

a second sensor configured to detect a monitoring evaporation rate of the evaporation material at a predetermined position; and

a controller unit configured to control a temperature of the source based on the monitoring evaporation rate.

8. The evaporation apparatus of claim 1, wherein the source is movable along a direction substantially orthogonal to a surface of the substrate on which the evaporation material is to be deposited.

9. The evaporation apparatus of claim 1, wherein the source is movable along a direction substantially parallel with a surface of the substrate on which the evaporation material is to be deposited.

10. An evaporation method, comprising:

evaporating an evaporation material to be deposited on a substrate by a source;

detecting evaporation rates of the evaporation material at a plurality of detection positions, wherein the plurality of detection positions are arranged along a detection line, and the detection line extends substantially orthogonal to a surface of the substrate on which the evaporation material is deposited;

estimating an evaporation angle based on the detected evaporation rates of the evaporation material at the plurality of detection positions; and

moving the source based on the estimated evaporation angle.

11. The evaporation method of claim 10, wherein the source has an opening from which the evaporation material is discharged, and a projection of the detection line on a projection plane is separated from a projection of the opening of the source on the projection plane, wherein the projection plane is substantially parallel with the surface of the substrate.

12. The evaporation method of claim 10, wherein the evaporation rates of the evaporation material at the plurality of detection positions is detected by a first sensor; and

the operation of detecting the evaporation rates of the evaporation material at the plurality of detection positions comprises moving the first sensor along the detection line.

13. The evaporation method of claim 10, wherein the operation of estimating the evaporation angle comprises comparing the detected evaporation rates with reference evaporation rates respectively, and the operation of moving the source is based on differences between the detected evaporation rates and the reference evaporation rates.

14. The evaporation method of claim 13, wherein the operation of moving the source comprises:

moving the source closer to the substrate in a direction orthogonal to the surface of the substrate on which the evaporation material is deposited when

the detected evaporation rates are greater than the reference evaporation rates respectively.

15. The evaporation method of claim 13, wherein the operation of moving the source comprises:

moving the source away from the substrate in a direction orthogonal to the surface of the substrate on which the evaporation material is deposited when the detected evaporation rates are smaller than the reference evaporation rates respectively.

16. The evaporation method of claim 13, wherein the operation of moving the source comprises:

moving the source away from the substrate in a direction parallel with the surface of the substrate on which the evaporation material is deposited when the detected evaporation rates are greater than the reference evaporation rates respectively.

17. The evaporation method of claim 13, wherein the operation of moving the source comprises:

moving the source closer to the substrate in a direction parallel with the surface of the substrate on which the evaporation material is deposited when the detected evaporation rates are smaller than the reference evaporation rates respectively.

18. The evaporation method of claim 10, wherein the operation of moving the source comprises:

moving the source closer to the substrate in a direction orthogonal to the surface of the substrate on which the evaporation material is deposited when the evaporation angle is greater than a reference evaporation angle.

19. The evaporation method of claim 10, wherein the operation of moving the source comprises:

moving the source away from the substrate in a direction orthogonal to the surface of the substrate on which the evaporation material is deposited when the evaporation angle is smaller than a reference evaporation angle.

20. The evaporation method of claim 10, wherein the operation of moving the source comprises:

moving the source away from the substrate in a direction parallel with the surface of the substrate on which the evaporation material is deposited when the evaporation angle is greater than a reference evaporation angle.

21. The evaporation method of claim 10, wherein the operation of moving the source comprises:

moving the source closer to the substrate in a direction parallel with the surface of the substrate on which the evaporation material is deposited when the evaporation angle is smaller than a reference evaporation angle.

22. The evaporation method of claim 10, further comprising:

detecting a monitoring evaporation rate of the evaporation material at a predetermined position; and

controlling a temperature of the source based on the monitoring evaporation rate.

23. The evaporation method of claim 22, the operation of controlling the temperature of the source further comprising:

increasing the temperature of the source when the monitoring evaporation rate decreases.

24. The evaporation method of claim 22, the operation of controlling the temperature of the source further comprising:

decreasing the temperature of the source when the monitoring evaporation rate increases.